

**Search Notes**

Application/Control No.

10/605,726

Examiner

Stephen W. Smoot

Applicant(s)/Patent under  
Reexamination

ZHU ET AL.

Art Unit

2813

**SEARCHED**

Class	Subclass	Date	Examiner
438	151	2/5/2005	SWS
438	270	2/5/2005	SWS
438	295	2/5/2005	SWS
438	300	2/5/2005	SWS
438	589	2/5/2005	SWS
438	595	2/5/2005	SWS
257	347	2/5/2005	SWS
257	387	2/5/2005	SWS
Updated	Above	5/26/2005	SWS

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
Same as Above		5/26/2005	SWS

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: SOI - BOX, SiGe, Silicon Epitaxial Layer;	2/5/2005	SWS
Elevated Source/Drain - Raised; Recessed Gate - Trench, Groove, Damascene, Inlaid.	2/5/2005	SWS
Updated Above Search	5/26/2005	SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	2/5/2005 5-26-05	SWS